

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-38. (Canceled)

39. (Previously Presented) An exposure method comprising:

providing a substrate such that the substrate is opposite to an optical member of an optical system and a nozzle member having at least any one of a supply outlet that supplies a liquid and a collection inlet that collects a liquid;

measuring a position of the nozzle member;

rotating the nozzle member around an axis perpendicular to an optical axis of the optical system based on the measured position of the nozzle member; and

exposing the substrate with an exposure beam through the optical system and the liquid.

40. (Previously Presented) An exposure method according to claim 39, wherein the measured position of the nozzle member includes a position around the axis perpendicular to the optical axis.

41. (Previously Presented) An exposure method according to claim 39, wherein the measured position of the nozzle member includes a position in a direction parallel to the optical axis.

42. (Previously Presented) An exposure method according to claim 41, further comprising moving the nozzle member in the direction parallel to the optical axis based on the measured position.

43. (Previously Presented) An exposure method according to claim 39, wherein the measured position of the nozzle member includes a position in a direction perpendicular to the optical axis.

44. (Previously Presented) An exposure method according to claim 43, further comprising moving the nozzle member in the direction perpendicular to the optical axis based on the measured position.

45. (Previously Presented) An exposure method according to claim 39, wherein the measured position of the nozzle member includes a position around the optical axis.

46. (Previously Presented) An exposure method according to claim 45, further comprising rotating the nozzle member around the optical axis based on the measured position.

47. (Previously Presented) An exposure method according to claim 39, wherein the nozzle member is moved under a feed-back control based on the measured position.

48. (Previously Presented) An exposure method according to claim 47, wherein the nozzle member is moved under a feed-forward control.

49. (New) A device fabricating method comprising:  
providing a substrate such that the substrate is opposite to an optical member of an optical system and a nozzle member having at least any one of a supply outlet that supplies a liquid and a collection inlet that collects a liquid;  
measuring a position of the nozzle member;  
rotating the nozzle member around an axis perpendicular to an optical axis of the optical system based on the measured position of the nozzle member;  
exposing the substrate with an exposure beam through the optical system and the liquid; and  
processing the exposed substrate.

50. (New) A device fabricating method according to claim 49, wherein the measured position of the nozzle member includes a position around the axis perpendicular to the optical axis.

51. (New) A device fabricating method according to claim 49, wherein the measured position of the nozzle member includes a position in a direction parallel to the optical axis.

52. (New) A device fabricating method according to claim 51, further comprising moving the nozzle member in the direction parallel to the optical axis based on the measured position.

53. (New) A device fabricating method according to claim 49, wherein the measured position of the nozzle member includes a position in a direction perpendicular to the optical axis.

54. (New) A device fabricating method according to claim 53, further comprising moving the nozzle member in the direction perpendicular to the optical axis based on the measured position.

55. (New) A device fabricating method according to claim 49, wherein the measured position of the nozzle member includes a position around the optical axis.

56. (New) A device fabricating method according to claim 55, further comprising rotating the nozzle member around the optical axis based on the measured position.

57. (New) A device fabricating method according to claim 49, wherein the nozzle member is moved under a feed-back control based on the measured position.

58. (New) A device fabricating method according to claim 57, wherein the nozzle member is moved under a feed-forward control.